

Figure 1. Data acquired with Ecopia AHT55T5 Hall effect measuring system for a magnetron sputtered Si-doped &-Ga2O3 grown at ECSU on Insulating Fe-doped &-Ga2O3 substrates from two different vendors.

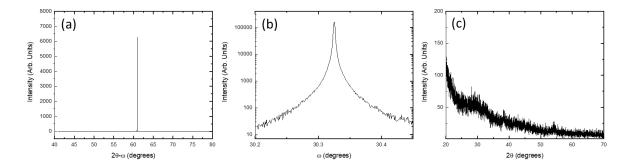


Figure 2. (a) Coupled, (b) omega and (c) 2-theta x-ray diffraction scan of Sn-doped Ga2O3 on (010)-oriented unintentionally doped Ga2O3 substrate.